Supporting Information

Sequential Deposition as a Route to Efficient Sb₂S₃ Solar Cells

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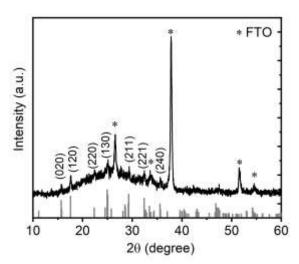


Figure S1. The detailed index of XRD pattern of Sb_2S_3 thin films prepared from 6 M TU deposited on $Sb(Ac)_3$ film annealed at 320 °C for 2 min.

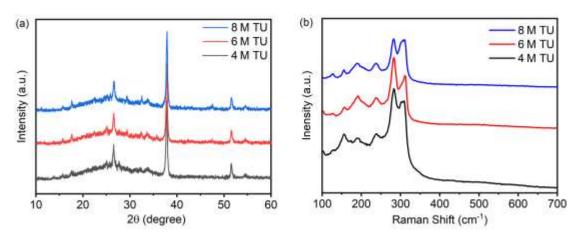


Figure S2. (a) The XRD spectra and (b) the Raman spectra of Sb_2S_3 thin films prepared from 4 M, 6 M and 8 M TU deposited on $Sb(Ac)_3$ film annealed at 320 °C for 2 min, respectively.

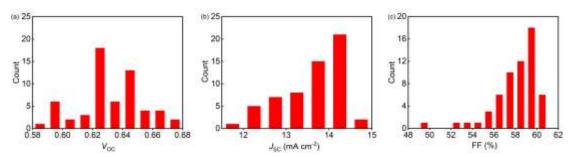


Figure S3. The histogram of device (a) $V_{\rm OC}$ (b) $J_{\rm SC}$, and (c) FF obtained from 59 individually fabricated solar cells with Sb₂S₃ thin films prepared from 6 M TU annealing at 320 °C for 2 min.

 $\underline{\text{Table S1. Photovoltaic parameters of the devices with different thicknesses of } Sb_2\underline{S}_3$

Thickness (nm)	PCE (%)	V _{OC} (V)	$J_{ m SC}$ (mA.cm ⁻²)	FF (%)
62	5.69	0.66	14.34	60.43
82	4.42	0.64	12.02	57.81
96	3.34	0.61	10.36	53.10
120	2.25	0.61	8.93	41.05

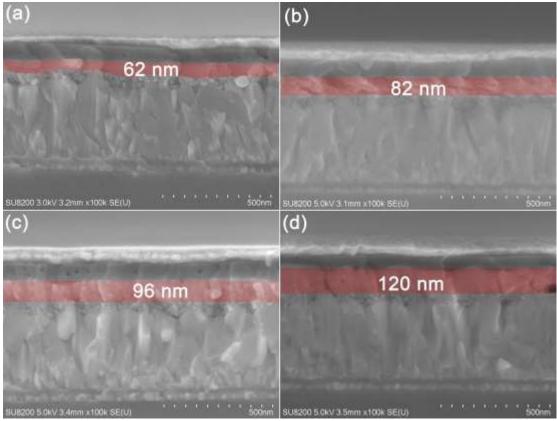


Figure S4. The different thicknesses of Sb_2S_3 films for devices according to SEM: (a) 62 nm, (b) 82 nm, (c) 96 nm and (d) 120 nm.



Figure S5. The digital image of Sb_2S_3 thin film prepared from 6 M TU annealing at 320 °C for 2 min.